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Methodology to Separate Channel Conductions of Two Level Vertically Stacked SOI Nanowire MOSFETs

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Abstract—This work proposes a new method for dissociating both channel conductions of two levels vertically stacked inversion mode nanowires (NWs) composed by a Gate-All-Around (GAA) level on top of an Ω-gate level. The proposed methodology is based on experimental measurements of the total drain current (I_{DS}) varying the back gate bias (V_B), aiming the extraction of carriers' mobility of each level separately. The methodology consists of three main steps and accounts for V_B influence on mobility. The behavior of non-stacked Ω-gate NWs are also discussed varying V_B through experimental measurements and tridimensional numerical simulations in order to sustain proposed expressions of mobility dependence on V_B for the bottom level of the stacked structure. Lower mobility was obtained for GAA in comparison to Ω-gate. The procedure was validated for a wide range of V_B and up to 150°C. Similar temperature dependence of mobility was observed for both Ω-gate and GAA levels.

Keywords—vertically stacked nanowires; SOI; mobility; back gate bias; tridimensional numerical simulations; temperature

I. INTRODUCTION

Multiple gate MOSFETs have attracted the interest of semiconductor industry due to strong immunity against short channel effects and great scalability because of improved electrostatic coupling [1]–[3]. Ω-gate and GAA MOSFETs with nanoscale cross-section, also denominated as nanowires, turned into candidates for future technological nodes due to their performance [2], [4]. Such devices are fabricated with close dimensions for both silicon thickness (H_{FIN}) and fin width (W_{FIN}), around 10nm. In order to fulfill higher drive current requests and increase the on-state current by footprint (I_{ON}/W_{FIN}), nanowires have been recently vertically stacked thanks to advances on tridimensional integration process [5]–[7]. Once vertically stacked NWs present overall channel width (W_{eff}) proportional to the number of stacked levels (or beams), these devices have higher aspect ratio, which is necessary for NWs to reach industrial targets for saturation current [8].

The implementation of vertically stacked NWs brings technological challenges such as the reduction of intrinsic parasitic capacitance and integration of carriers' mobility boosters. These problems have been recently addressed by the innovative structure fabricated at CEA-LETI, combining inner spacers and SiGe source/drain in vertically stacked p-type NW MOSFETs [7]. The overall effective mobility of these stacked NWs was investigated in [9], while [10] presented a methodology to perform individual electrical characterization of each NW level including explicit expressions for the low field mobility (μ_0) and mobility degradation coefficients (θ_1 and θ_2) dependence on V_B. Once the first work aiming to separate

the channel conductions of staked multiple gate devices using V_B [11] does not take into account transport parameters dependence on the back bias, the methodology proposed in [10] improves [11]. In this work, we extend [10] by including experimental measurements and tridimensional numerical simulations of non-stacked Ω-gate NWs varying V_B in order to explain physical effects in the potential, electric field and holes mobility under different back bias conditions. Such explanations are important to understand the vertically stacked NWs behavior and, therefore, sustain the expressions used for mobility dependence on V_B in the proposed methodology for individual electrical characterization, once the bottom level of the stacked structure is Ω-shaped. Moreover, this work brings deeper details of the proposed methodology step by step, so it can be easily reproduced. Discussions concerning temperature influence on V_B dependence are also presented in this work.

The paper is organized as follows: Section II details the devices characteristics for both stacked (Section II-A) and non-stacked NWs (Section II-B). Section III presents the main physical effects of applying V_B on mobility of non-stacked Ω-gate NWs (Section III-A), the proposed methodology to dissociate channel conductions of two levels vertically stacked NWs (Section III-B) and temperature influence on V_B dependence (section III-C). Finally, Section IV points out the main conclusions of this work.

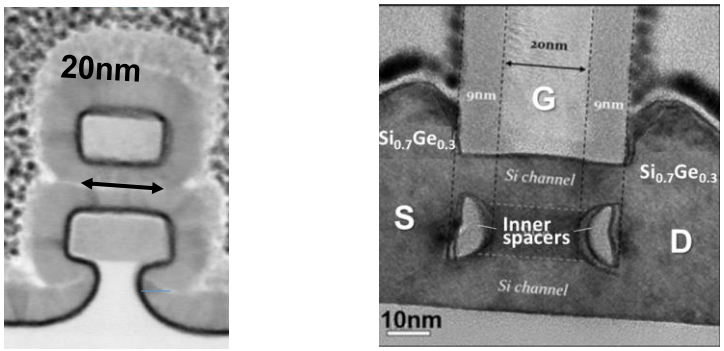
II. DEVICES CHARACTERISTICS

A. Vertically stacked NWs

Transistors are [110]-oriented vertically stacked p-type inversion mode nanowires MOSFETs with two levels, being the bottom level Ω-gated and the top level GAA. Figure 1 shows Transmission Electron Microscopy (TEM) images of the studied stacked NWs cross section (a) and the longitudinal section (b). Usually the vertically stacked NWs have an Ω-gated bottom level while the upper levels are GAA because the fabrication process starts from Fully Depleted (FD) SOI wafers. The first Si channel lies on top of the buried oxide and the upper channels are fabricated on top of SiGe layers, which are replaced after selective etching, giving place to the surrounded gate stack of GAA NWs. From Figure 1.a, it is possible to note that the front gate of the bottom NW is electrostatically coupled with the back gate. Although narrow triple gate MOSFETs present lower back gate bias (V_B) influence in comparison to planar MOSFETs [12], the potential lines coming from the back gate manage to reach the Si channel through the interface between Si and buried oxide. On the other hand, the top NW is independent of V_B because it is surrounded by the gate stack. Despite the lower impact of V_B over the electrical parameters of narrow Ω-NWs, since the bottom NW is V_B dependent while the top one is V_B independent, back biasing can be used as a tool to separate the channels conduction. The interest of using back bias in this work is attached to the methodology proposed in Section III to perform individual electrical characterization for future technology optimization.

Devices have been fabricated at CEA-LETI, starting from Silicon-On-Insulator (SOI) wafers with 145nm buried oxide thickness (t_{BOX}) and using a replacement metal gate (RMG) process to obtain a gate stack composed by HfO_2/TiN/W, resulting in effective oxide thickness (EOT) of 1.15nm. Each level has a 10nm thick undoped Si channel and both levels are attached by common metal gate and $Si_{0.7}Ge_{0.3}$:B raised source/drain (B doping level in the order of few $10^{20}cm^{-3}$ [13]). The transistors have been

fabricated in multi finger structures with 50 fins in parallel and channel length (L) of 100nm. Further fabrication details of the stacked-NWs studied in this work can be found in [7].



(a) (b)

Figure 1. Vertically stacked SOI nanowire cross section (a) and longitudinal section (b) TEM images.

Figure 2 presents drain current, I_{DS} (a), transconductance, g_m (b), and its derivative, $\delta g_m/\delta V_{GS}$ (c), as a function of the front gate voltage (V_{GS}) for stacked NW with W_{FIN} = 15nm and L = 100nm, at low drain voltage (V_{DS} = -40mV), varying V_B from -90V to 90V. In these figures the curves with symbols refer to V_B = 0V. During the measurements, V_B was applied at the substrate of the whole wafer, which is isolated from the active channels by the thick buried oxide. Although ±90V may seem like extremely high bias condition, it is important to remember that t_{BOX} = 145nm. For simplicity, considering the same linear potential drop across the front and back interface, 90V applied at 145nm-thick oxide would correspond to ~0.7V applied at the same oxide with thickness of 1.15nm. The applied back bias values must be adjusted according to the technology of the studied SOI MOSFET to avoid reliability and degradation issues due to high vertical electric field.

Figure 2.a shows expected shift of curves to the left as V_B increases due to threshold voltage (V_{TH}) variation. Moreover, small back conduction is noted in the subthreshold region of logarithmic curves for negative back gate values.

Figure 2.b shows two distinguished peaks for g_m depending on V_B. Results suggests some V_{TH} mismatch between bottom and top levels once the two peaks are still slightly perceived at V_B = 0V, the first for V_{GS} ≅ -0.4V and the second for V_{GS} ≅ -0.75V. Two effects are observed and overlapped. First, the g_m peak decreases with V_B increase for negative values (dashed lines) and for high positive V_B (higher than 50V). Second, for sufficiently low V_B a second g_m peak appears at higher V_{GS} voltages. This second g_m peak presents the opposite behavior from 0V < V_B < 50V. The effect that explains the first behavior is related to the effective mobility changing with V_B, which will be detailed in Section III-A. The second effect happens due to V_{TH} mismatch, the closer both threshold voltages get, the higher the transconductance, once both conductions are overlapped from their starting point, where no strong mobility degradation is observed yet due to surface roughness.

Figure 2.c confirms the existence of V_{TH} mismatch between top and bottom levels at V_B = 0V. The constant peak in Figure 2.c is insensitive to V_B and related to the threshold voltage of the top NW (V_{TH_GAA}), while the other one is sensitive to V_B and corresponds to the threshold voltage of the bottom Ω-NW ($V_{TH_\Omega G}$). No peak is observed due to back conduction because of its small contribution, as

indicated in Figure 2.a and expected in narrow Ω-NWs. V_{TH} mismatches could be related to charge traps in the GAA-NW, which presents much lower V_{TH} and is more susceptible to defects after RMG process fabrication in comparison to the bottom level.

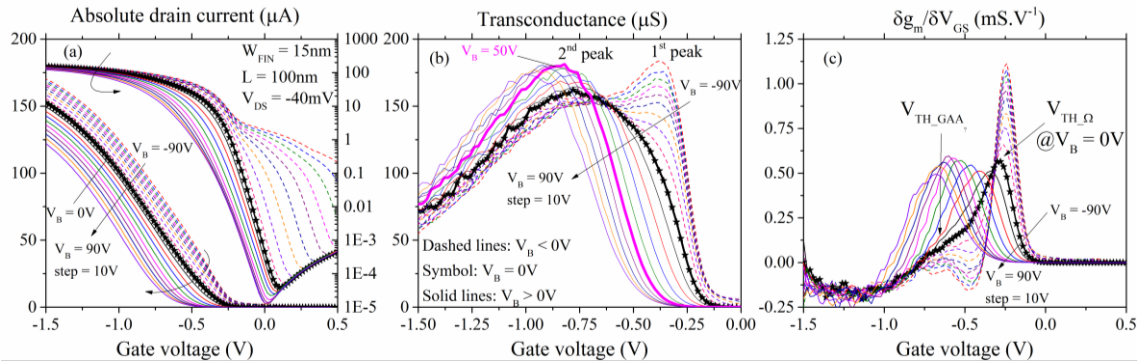


Figure 2. $|I_{DS}|$ (a), g_m (b) and $|\delta g_m/\delta V_{GS}|$ (c) as a function of V_{GS} for stacked NW with W_{FIN} = 15nm, L = 100nm, V_{DS} = -40mV and V_B from -90 to 90V.

Figure 3 shows threshold voltage, V_{TH} (a), and subthreshold slope, S (b), as a function of V_B for stacked NWs with W_{FIN} = 15 and 25nm and L = 100nm, at V_{DS} = -40mV. The threshold voltage has been extracted by the double derivative method. The subthreshold slope has been extracted from $\partial V_{GS}/\partial(\log I_{DS})$ curves, considering an average around the minimum value to account for ~1-2 decades of I_{DS}. Figure 3.a presents V_{TH} for both bottom ($V_{TH_\Omega G}$) and top (V_{TH_GAA}) NWs extracted from $\partial g_m/\partial V_{GS}$ peaks in Figure 2.c. Threshold voltage mismatches between bottom and top NWs are found to be 0.32 and 0.34V for W_{FIN} = 15 and 25nm, respectively, at V_B = 0V. It is observed that $V_{TH_\Omega G}$ exhibits a plateau for V_B < -10V because the back interface of the bottom NW operates in inversion, which degrades the overall subthreshold slope. For V_B > -10V, the bottom NW enters in full depletion and $V_{TH_\Omega G}$ decreases linearly with V_B increase, while V_{TH_GAA} remains constant once the top NW is V_B independent. Due to thin silicon layer, the bottom NW never reaches accumulation [14]. At V_B = 50V, $V_{TH_\Omega G}$ = V_{TH_GAA}. The NW level with lower $|V_{TH}|$ conducts at lower $|V_{GS}|$ and, therefore, dominates the subthreshold slope behavior of the overall structure. The I_{DS} of the NW level with higher $|V_{TH}|$ is orders of magnitude lower comparing to the other NW level, at a given V_{GS} in the subthreshold regime, so its subthreshold characteristic is hidden in the I-V curve of the overall structure. For V_B > 50V, $|V_{TH_\Omega G}|$ > $|V_{TH_GAA}|$, thus the subthreshold characteristics observed in I_{DS} are determined by the GAA-NW. This explanation is consistent with constant S results varying V_B above 50V, because GAA characteristics are independent of V_B.

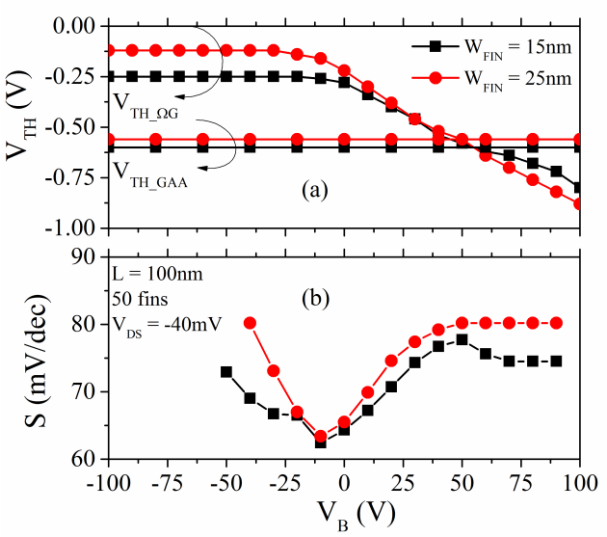
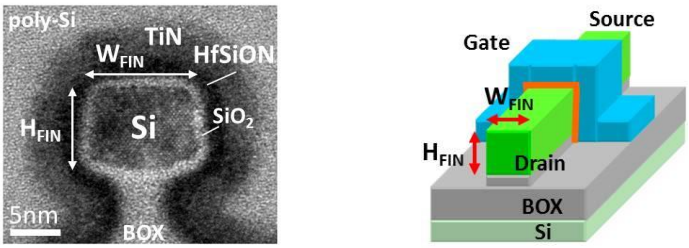


Figure 3. V_{TH} and S as a function of V_B for stacked NWs with W_{FIN} = 15 and 25nm, L = 100nm and V_{DS} = -40mV.

B. Non-stacked Ω-NWs

Once the overall behavior of the stacked structure varying V_B is determined by the bottom level, non-stacked Ω-NWs will be also studied in order to better understand the stacked NWs behavior with V_B. Transistors are silicon [110]-oriented Ω-NWs SOI MOSFETs in multi finger structures with 10 fins in parallel, H_{FIN} = 11nm, L = 100nm, t_{BOX} = 145nm and gate stack composed by HfSiON/TiN (EOT = 1.4nm). Figure 4 shows TEM image (a) and schematic (b) of the devices fabricated at CEA–Leti [15], [16].



(a) (b)

Figure 4. Non-stacked SOI NW cross section TEM image (a) and schematic (b).

Figure 5 presents I_{DS} (a) and g_m (b) as a function of V_{GS} for non-stacked NW with W_{FIN} = 15nm and L = 100nm, at V_{DS} = -40mV, varying V_B from -80V to 80V. Although Figure 5.a shows the same behavior for I_{DS} with V_B as in Figure 2.a, a single g_m peak is observed in Figure 5.b, once the non-stacked transistor is a single level NW. As V_B increases, the maximum g_m decreases in a practically constant rate, suggesting stronger mobility degradation effect as V_B gets higher. Such behavior is coherent with results in Figure 2.b for negative back bias. The physical effects resulted from V_B influence will be discussed in details in Section III-A.

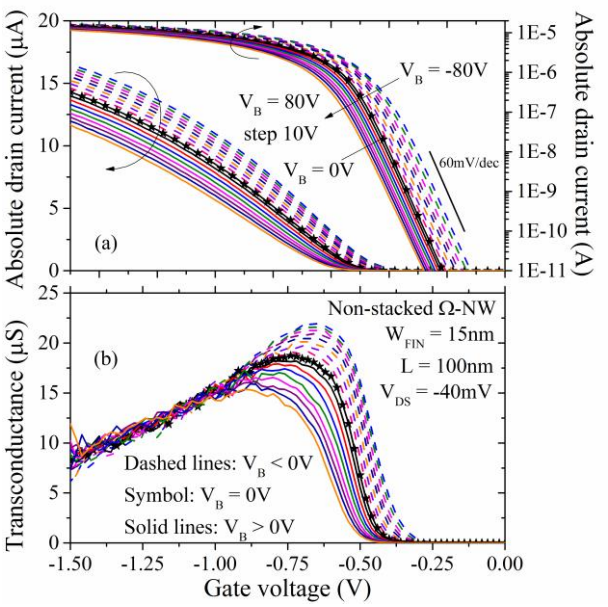


Figure 5. $|I_{DS}|$ (a) and g_m (b) as a function of V_{GS} for non-stacked NW with W_{FIN} = 15nm, L = 100nm, V_{DS} = -40mV and V_B from -80 to 80V.

III. Results and Discussion

A. Back bias dependence for non-stacked Ω-NWs

Tridimensional numerical simulations were performed in Sentaurus Device Simulator, from Synopsys [17]. Same dimensions and materials as in fabricated Ω-NWs were used to build the simulated structures in Sentaurus Process [18], as shown in Figure 6. Transport parameters of *Inversion and Accumulation Layer Mobility Model* were calibrated according to measured I-V curves in Figure 5. Fixed charges of $6\times10^{12}cm^{-2}$ were placed at the silicon/buried oxide interface to adjust the threshold voltage of the back interface. Moreover, simulations account for the following physical effects: mobility degradation due to vertical and lateral electric fields, Shockley-Read-Hall effect and Auger recombination, bandgap narrowing dependence on temperature and doping, Fermi statistics and density gradient quantization.

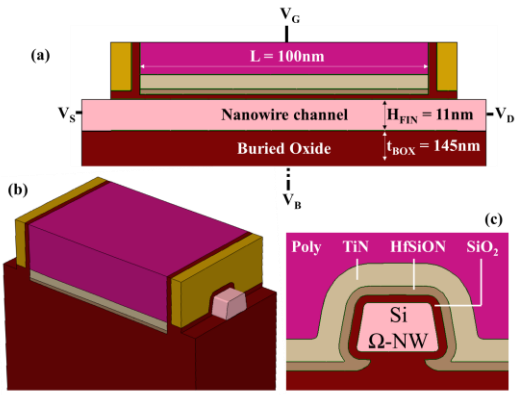


Figure 6. Ω-gate nanowire TCAD structure originated from Sentaurus Process and used for tridimensional numerical simulation. Longitudinal section (a), perspective (b) and cross section (c).

Figure 7 presents simulated results extracted along the vertical cut of non-stacked NW cross-section for the electrostatic potential (a), electric field (b) and holes concentration (c) at gate voltage overdrive (V_{GT} = V_{GS} − V_{TH}) of -150mV, V_{DS} = -40mV and V_B ranging from -100V to 100V. Height = 0nm indicates silicon/buried oxide interface and Height = 10nm indicates silicon/front oxide interface. Figure 7.a shows inversion at the front gate for all V_B values and back inversion for V_B = -80V and -100V, where the back bias is negative enough to induce back conduction. The inflection point that separates inversion from depletion appears around 7.5nm far from the silicon/buried oxide interface indicating that inversion layer occurs up to 2.5nm far from the front interface. These effects are clearer in Figure 7.c, where the front and back conductions are observed by the peaks of holes concentration, around 2nm close to the front interface for V_B from 100V to -60V and then a second peak appearing close to the back interface for V_B = -80V and -100V. Figure 7.a also shows the electrostatic potential decrease with V_B increase at the front interface and opposite behavior at the back interface. Potential changing is reflected in the holes concentration in Figure 7.c, where the peak at the front interface increases with V_B increase at the front interface and opposite behavior is verified at the back interface.

Figure 7.b shows the electric field increase with V_B increase, which leads to stronger mobility degradation [1]. Moreover, it is observed in Figure 7.c that the conduction peak moves into the center of the silicon layer with V_B reduction. The center of the transistor should present higher effective mobility due to smaller electric field (see Figure 7.b) and lower surface roughness scattering in the case of fabricated devices. Indeed, as discussed in [19], the inversion charge distribution in the channel is modulated by V_B. Therefore, after the analysis of Figure 7, it is possible to state that the effective mobility is expected to reduce with V_B increase because of holes concentration increase and its position change along the NW channel.

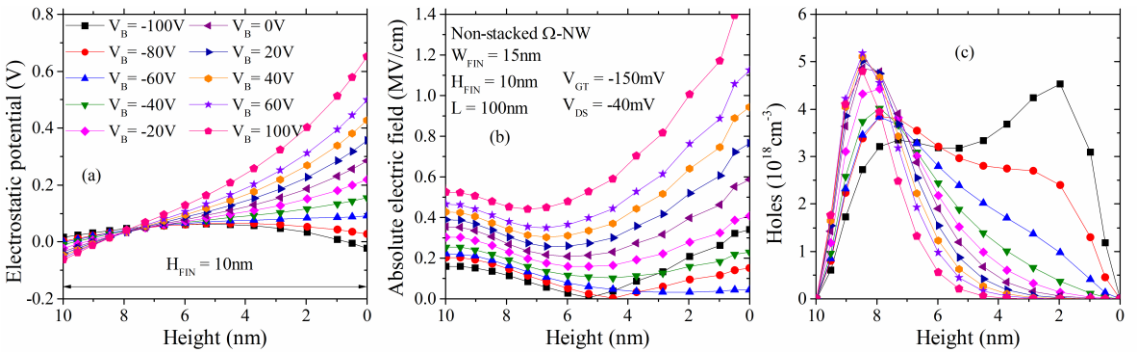


Figure 7. Simulated results for the electrostatic potential (a), electric field (b) and holes concentration (c) as a funtion of fin height for non-stacked NW with W_{FIN} = 15nm, H_{FIN} = 10nm, L = 100nm, V_{DS} = -40mV, V_{GT} = -150mV and V_B from -100 to 100V.

Figure 8 shows holes mobility along the vertical cut of non-stacked NW cross-section at V_{GT} = -150mV, V_{DS} = -40mV and V_B varying from -100V to 100V. Holes mobility follows the inverse of the electric field behavior, increasing with V_B decrease and being higher in the center of the silicon layer. In practice, comparing to mobility closer to the front oxide interface, mobility in the center and closer to the buried oxide of fabricated devices must be even higher than those in simulations, because of smaller defects and better interface quality at the second interface [20], which are not considered in these simulations.

Besides, it is observed that holes mobility closer to the buried oxide decreases with V_B decrease for V_B = -80V and -100V, which happens because of holes concentration increase in this region, where some back conduction starts to appear, as verified in Figure 7.c.

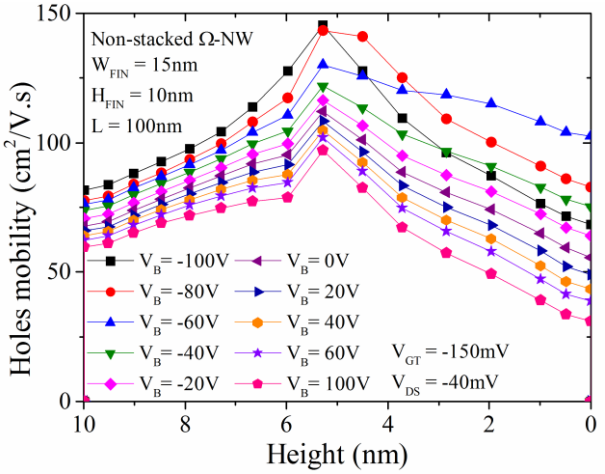


Figure 8. Simulated results for holes mobility as a funtion of fin height for non-stacked NW with W_{FIN} = 15nm, H_{FIN} = 10nm, L = 100nm, V_{DS} = -40mV, V_{GT} = -150mV and V_B from -100 to 100V.

Figure 9 shows μ_{eff} as a function of V_{GS} for simulated non-stacked NW varying V_B from -100V to 100V. Results were calculated by split C-V technique [21]. As expected from g_m results in Figure 5 and explained by results in Figure 7, the effective mobility shows significant degradation with V_B increase (up to 37% considering maximum mobility variation from V_B = -100V to 100V). Curves shift to the right indicate V_{TH} decrease with V_B increase, where $\Delta V_{TH}/\Delta V_B$ has been extracted around -1.1mV/V from I-V simulations. Similar result has been obtained from measurements in Figure 5, where $\Delta V_{TH}/\Delta V_B$ = -1.0mV/V. Figure 9 also shows that μ_{eff} differences among curves with different V_B reduces with V_{GS} increase, indicating that first order mobility degradation coefficient (θ_1) increases with V_B reduction. This assumption is confirmed in Section III-B after complete extraction of mobility parameters through the proposed methodology.

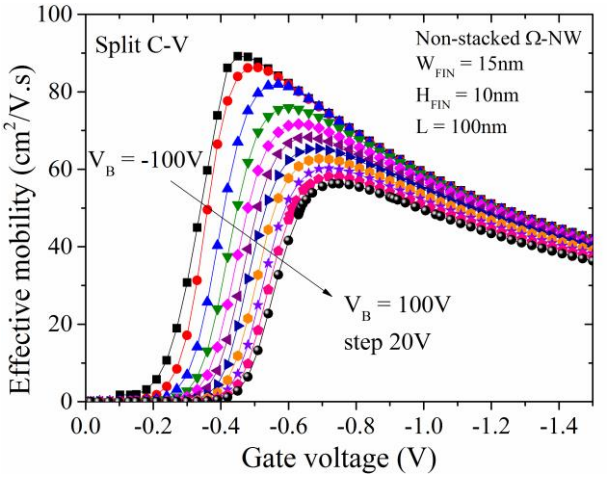


Figure 9. Simulated results for μ_{eff} extracted by split C-V method as a funtion of V_{GS} for non-stacked NW with W_{FIN} = 15nm, H_{FIN} = 10nm, L = 100nm, V_B from -100 to 100V.

Symbols in Figure 10 show extracted μ_0 as a function of V_B for simulated and measured non-stacked NWs. Dashed lines indicate linear fitting of data points. For simulations, results were obtained by taking the maximum μ_{eff} from Figure 9, calculated from split C-V method. For measurements, as devices present small capacitance level, split C-V could not be applied and results were obtained through Y-function method [22], where the low field mobility represents μ_{eff} at V_{GT} = 0V. Once Y-function method do not predict Coulomb scattering mobility degradation [23], Y-function μ_0 results are expected to be slightly higher than those extracted by split C-V. Independent on the methodology, both simulations and measurements can be represented by linear expressions with acceptable errors (smaller than 5% and 8% for simulations and measurements, respectively). Moreover, similar μ_0 dependence on V_B is observed for both simulations (slope = -0.17cm^2/V^2.s) and measurements (slope = -0.21cm^2/V^2.s), as expected after I-V calibration. Higher slope obtained for measurements could be related to the better interface quality at the second interface in comparison to the first interface, which increases even more the effective mobility when the inversion channel shifts to the center of Si layer.

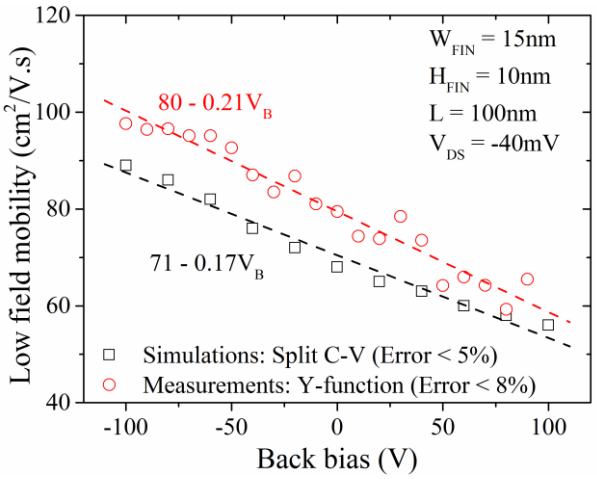


Figure 10. μ_0 as a funtion of V_B for simulated and measured non-stacked NWs with W_{FIN} = 15nm, H_{FIN} = 10nm, L = 100nm and V_{DS} = -40mV. Dashed lines indicate linear regression of data points, where errors obtained are smaller than 5% and 8% for simulations and measurements, respectively.

B. Methodology for mobility dissosiation in stacked NWs

Once measured $I_{DS} - V_{GS}$ curves varying V_B are obtained for stacked NWs, it is possible to dissociate the bottom and top levels mobility contribution in 3 steps, by using the following proposed methodology. In order to show the extended validity of the proposed methodology, a wide range and large number of V_B values were taken into account. Since linear equations are used to express mobility dependence on V_B, the technique can also be successfully employed with much fewer $I_{DS} - V_{GS}$ curves and lower V_B values. Concerning the range of geometrical parameters for the application of the proposed methodology, W_{FIN} and H_{FIN} must be equal or larger than 10nm, so quantum effects can be considered negligible. Moreover, the models do not account for short channel effects, so nanowires with long channel length are desired.

Step 1.

In order to obtain the overall parameters related to the sum of contributions of Ω- and GAA-NWs, Y-function method is applied to the measured I_{DS}. At this step, V_{GS} range where Y-function is applied must be chosen to capture the back bias influence on low field mobility of the Ω-NW. From the dashed lines in Figure 2.b, where $V_B < 0V$, it is observed that g_m peak significantly decreases with V_B increase on the same way as observed in Figure 5.b for non-stacked NW. Moreover, Figure 3 shows that negative values of V_B lead to constant V_{TH_Ω} and V_{TH_GAA}. When both top and bottom levels present constant threshold voltage with V_B variation, $I_{DS_\Omega G}$ and I_{DS_GAA} do not shift along V_{GS}. In this case, the overlap between the two currents must not influence the extraction of V_B dependence. Therefore, g_m variation at negative V_B should be only linked to μ_{eff} effect. Figure 11 shows μ_0 and first and second order mobility degradation coefficients (θ_1 and θ_2) extracted from Y-function, varying V_B. The gate capacitance per unit of area (C_{OX}) and the effective channel width (W_{eff}) used in Y-function methodology are $2.7\times10^{-6}F/cm^2$ and $8.5\times10^{-6}cm$, respectively. Symbols represent the extracted results and lines indicate linear regression of data points. Figure 12 shows g_m as a function of V_{GS} for the stacked NW, where symbols indicate the measurements and the lines were obtained from Y-function expressions, using the extracted parameters shown in Figure 11. The agreement among lines and symbols in Figure 12 indicates that V_{GS} range chosen for the application of the Y-function methodology (highlighted in yellow) clearly captures g_m variation with V_B.

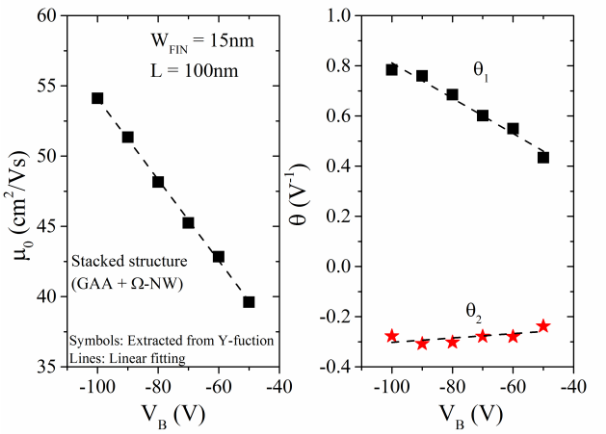


Figure 11. Step 1. Overall low field mobility (a) and mobility degradation coefficients (b) as a function of V_B for vertically stacked NWs with W_{FIN} = 15nm and L = 100nm. Results were extracted from the total I_{DS}, which corresponds to the characteristics of the whole stacked structure, i.e. sum of GAA and Ω-NW contributions.

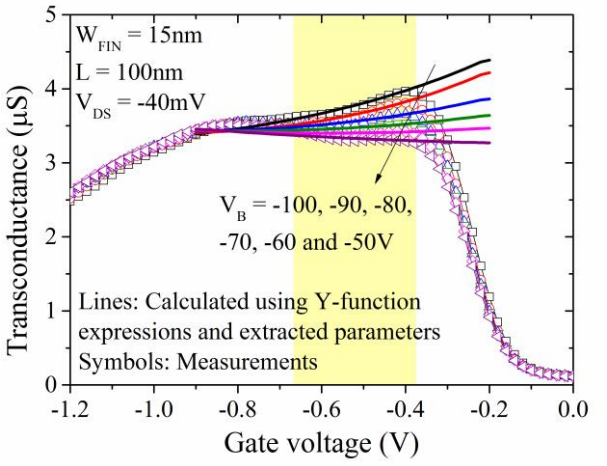


Figure 12. Step 1. Measurements and Y-function model results of g_m as a function of V_{GS} for stacked NW with W_{FIN} = 15nm, L = 100nm and V_{DS} = -40mV. The area painted in yellow indicates the V_{GS} range chosen to apply the Y-function methodology.

As previously discussed in Section III-A, a linear dependence between mobility parameters and V_B is expected for Ω-NWs. Moreover, linear expressions can be considered with small errors for a wide V_B range. Therefore, the bottom level first and second order mobility degradation coefficients and low field mobility can be written as $\theta_{1,\Omega G} = A_{\theta 1} + a_{\theta 1} \times V_B$; $\theta_{2,\Omega G} = B_{\theta 2} + b_{\theta 2} \times V_B$ and $\mu_{0,\Omega G} = C_{\mu 0} + c_{\mu 0} \times V_B$. On the other hand, the GAA level mobility parameters are constants and given by $\theta_{1,GAA}$, $\theta_{2,GAA}$ and $\mu_{0,GAA}$.
From Figure 11, the linear fittings of data points lead to the extraction of slope and intercept, where the slopes indicate the V_B dependence of the parameters. As the GAA-NW contribution does not change with V_B, slopes extracted from Figure 11 can be exclusively attributed to the bottom Ω-NW and correspond to $a_{\theta 1}$, $b_{\theta 2}$ and $c_{\mu 0}$.

Step 2.

For $V_B \geq 0$, as there is no back conduction, the stacked NW drain current can be written as

$$I_{DS}(V_B \geq 0) = I_{DS,\Omega G}(V_B) + I_{DS,GAA} \quad (1)$$

where the drain currents of Ω- and GAA-NWs, at low V_{DS}, are given by

$$I_{DS,\Omega G}(V_B) = \frac{W_{eff,\Omega G} \times C_{OX}}{L} \frac{\mu_{0,\Omega G}(V_B) \times V_{GT,\Omega G}(V_B) \times V_{DS}}{1 + \theta_{1,\Omega G}(V_B) \times V_{GT,\Omega G}(V_B) + \theta_{2,\Omega G}(V_B) \times V_{GT,\Omega G}^2(V_B)} \quad (2)$$

$$I_{DS,GAA} = \frac{W_{eff,GAA} \times C_{OX}}{L} \frac{\mu_{0,GAA} \times V_{GT,GAA} \times V_{DS}}{1 + \theta_{1,GAA} \times V_{GT,GAA} + \theta_{2,GAA} \times V_{GT,GAA}^2} \quad (3)$$

Considering that mismatches of W_{FIN} and H_{FIN} between bottom and top levels are negligible, as suggested by TEM images (Figure 1), the effective channel widths are $W_{eff,\Omega G} = (2H_{FIN} + W_{FIN})$ and $W_{eff,GAA} = (2H_{FIN} + 2W_{FIN})$. For the sake of simplicity, we approximate the W_{eff} expression of the Ω-NW to the one that describes a triple gate transistor. In practice, the top surface of the Ω-NW is slightly smaller than

W_{FIN}, which decreases W_{eff} in few nanometers. Opposite effect is observed for the bottom surface, which is partially surrounded by the gate. Since the opposite characteristics may compensate each other, the calculated W_{eff} should not present strong deviation in comparison to the real dimension. Good accuracy is desired when calculating W_{eff}, because an error of +X% in W_{eff} results in an error of –X% in $\mu_0/(1 + \theta_1 V_{GT} + \theta_2 V_{GT}^2)$. This error of –X% should be distributed among the three parameters. For the studied stacked NW with $W_{FIN} = 1.5\times10^{-6}$cm and $H_{FIN} = 1.0\times10^{-6}$cm, $W_{eff,\Omega G} = 3.5\times10^{-6}$cm and $W_{eff,GAA} = 5.0\times10^{-6}$cm.

Subtracting (1) at a given $V_{B1} \geq 0$ from (1) at $V_{B2} > V_{B1}$, the resulting current will only depend on $I_{DS,\Omega G}$, once $I_{DS,GAA}$ is constant with V_B and annulated by the subtraction. If the difference between the total currents at two different V_B values is called $\Delta I_{DS}(V_B)$, then

$$\Delta I_{DS}(V_B) = I_{DS}(V_{B1}\geq 0) - I_{DS}(V_{B2}>V_{B1}) = I_{DS,\Omega G}(V_{B1}) - I_{DS,\Omega G}(V_{B2}) \quad (4)$$

Fitting (4) to experimental measurements allow determining the remaining mobility parameters for the bottom Ω-NW, which are the intercepts $A_{\theta 1}$, $B_{\theta 2}$ and $C_{\mu 0}$. Figure 13 shows ΔI_{DS} as a function of V_{GS} for V_{B1} = 0V and several positive V_{B2} values, ranging from 10V to 90V. Good agreement is obtained comparing measurements and fitted expression (4).

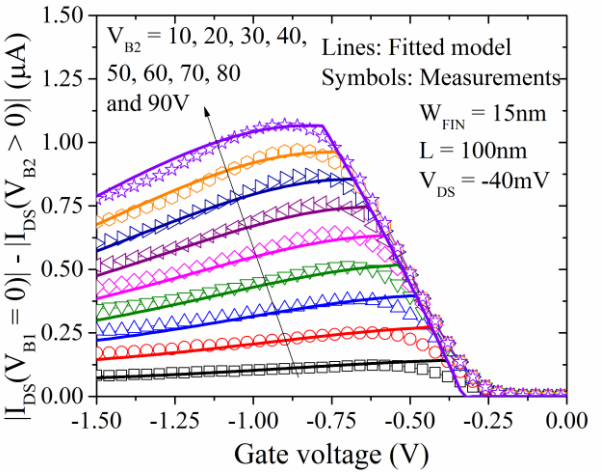


Figure 13. Step 2. Measurements and model results of ΔI_{DS} as a function of V_{GS} for stacked NW with W_{FIN} = 15nm, L = 100nm and V_{DS} = -40mV.

Step 3.

After step 2, $I_{DS,\Omega G}$ can be fully calculated, once all parameters for the bottom level are determined. Fitting I_{DS} measurements to (1), it is possible to extract the top level parameters $\theta_{1,GAA}$, $\theta_{2,GAA}$ and $\mu_{0,GAA}$. Figure 14 shows I_{DS} measured curves and fitted expression (1) for positive V_B ranging from 10V to 90V. It is important to keep positive V_B values at this step because there is no back conduction component comprised in the total current. Good agreement is obtained for all V_B values comparing measurements and fitted model.

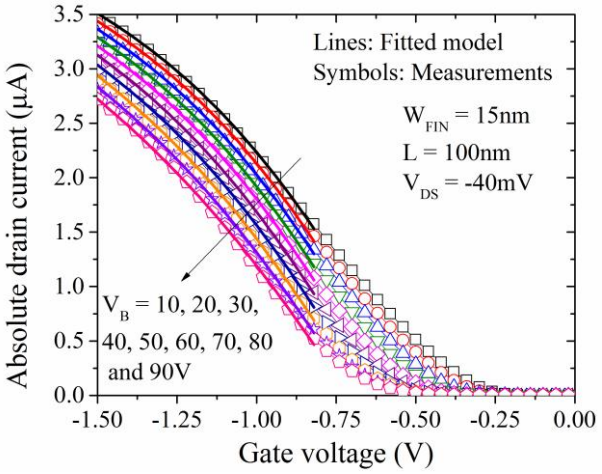


Figure 14. Step 3. Measurements and model results of $|I_{DS}|$ as a function of V_{GS} for stacked NW with W_{FIN} = 15nm, L = 100nm and V_{DS} = -40mV.

Figure 15 presents the schematics of the entire procedure, highlighting all the extracted parameters and respective steps.

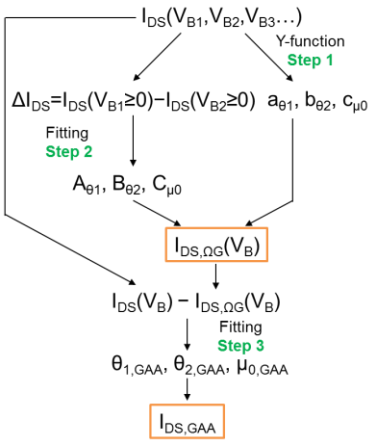


Figure 15. Schematic representation of the proposed method highlighting steps 1 to 3.

Figure 16 presents the obtained parameters for both Ω- and GAA-NWs of the stacked structure. Similar $\mu_{0,\Omega G}$ is found by comparing the stacked bottom level ($79 - 0.26V_B$) to the non-stacked Ω-NW in Figure 10 ($80 - 0.21V_B$), corroborating with the validity of the proposed method. Lower μ_0 is obtained for GAA-NW in comparison to bottom Ω-NW, which could be related to the defects that might have shifted its V_{TH} (Figure 3). Besides, lower mobility is expected for GAA in comparison to Ω-shaped structures due to detrimental stronger contribution of (100)/[110] surface for holes [24].

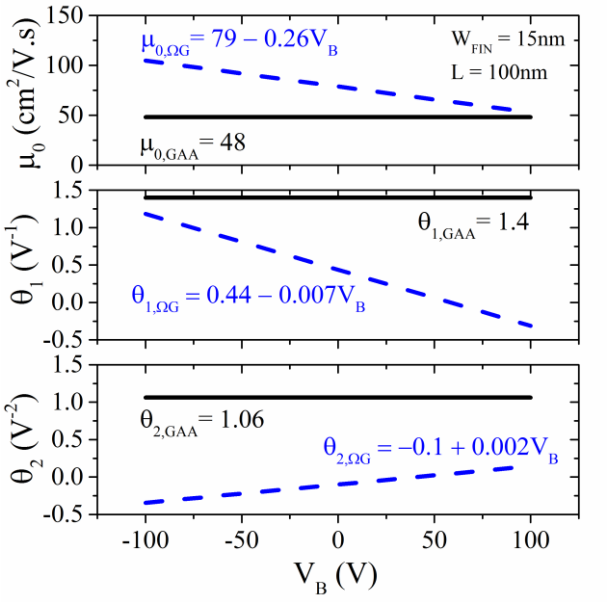


Figure 16. Parameters extracted through the proposed methodology for stacked NWs with W_{FIN} = 15nm and L = 100nm.

In case of many GAA stacked levels over one Ω-gate level, it would still be possible to apply the proposed methodology and extract the mobility parameters of the Ω-NW. If an approximation where all GAA-NWs present similar characteristics (dimensions, defects and mobility scattering) can be considered reliable for a given technology, the mobility parameters could be also extracted for the GAA levels. Since uniformity for GAA-NWs is hard to obtain during the fabrication process of several stacked levels, the technique applicability would depend on how interesting the extraction of average behaviors for the GAA-NWs would be.

C. Temperature dependence for stacked NWs

By applying the proposed methodology in stacked NWs under different temperature conditions, it is possible to study the temperature dependence on the back bias influence on mobility. Stacked NWs have been measured from 25°C up to 150°C and μ_0 has been extracted for both bottom and top levels through the proposed method. It is important to mention that nanowires present quantum confinement effects at cryogenic operation [25], so the methodology should be no longer valid at very low temperatures. Figure 17 shows results of the low field mobility as a function of V_B at different T, for the bottom Ω-NW with W_{FIN} = 25nm, L = 100nm and V_{DS} = -40mV. It is observed the expected mobility decrease with T increase [26], reducing from 68cm^2/V.s (at 25°C and V_B = 0V) to 52cm^2/V.s (at 150°C and V_B = 0V), which represents 21% of degradation. Lower mobility obtained for W_{FIN} = 25nm (68cm^2/V.s at 25°C and V_B = 0V) in comparison to W_{FIN} = 15nm (79cm^2/V.s at 25°C and V_B = 0V, in Figure 16) is due to higher (100)/[110] surface contribution, as already discussed in [9], [24]. Moreover, Figure 17 shows that μ_0 slopes significantly decrease with T increase, suggesting stronger back bias influence at lower T conditions.

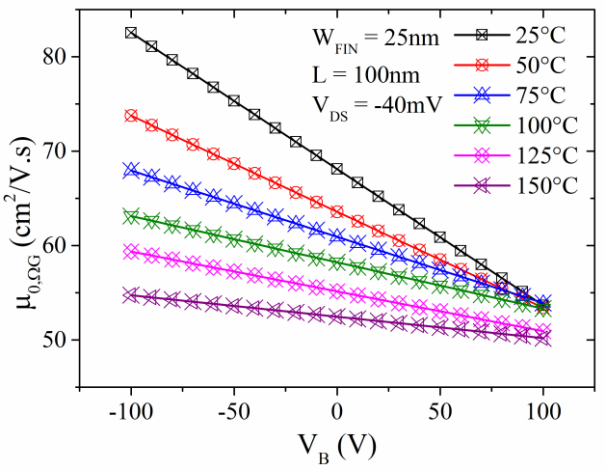


Figure 17. Extracted $\mu_{0,\Omega G}$ as a function of V_B for bottom Ω-NW of stacked transistor with W_{FIN} = 25nm, L = 100nm and V_{DS} = -40mV. Temperature varies from 25°C to 150°C.

Figure 18 presents μ_0 as a function of T for both top and bottom NWs, indicating clear temperature influence on μ_0 dependence on V_B. At V_B = 0V, both Ω- and GAA-NWs present similar μ_0 slope with temperature variation ($\Delta\mu_0/\Delta T$), -0.12cm²/V.s.°C and -0.11cm²/V.s.°C, respectively. As V_B decrease pushes the inversion channel to the center of the silicon layer, as studied in Figure 7.c, reduced surface roughness contribution and higher phonon scattering contribution are expected. Unlike surface roughness scattering, phonon scattering is high T dependent, which leads to strong μ_0 T-dependence with V_B. For positive V_B, carriers are pushed against the interface and surface roughness limited contribution is dominant. Since this mobility degradation mechanism is T independent, μ_0 is almost constant varying T. The same trend for $\Delta\mu_0/\Delta T$ with V_B variation has been observed in non-stacked Ω-NWs MOSFETs, as indicated in Table 1. Results of $\Delta\mu_0/\Delta T$ for the bottom level of stacked NW in Figure 18 and non-stacked Ω-NW with W_{FIN} = 20nm, L = 100nm have been summarized in Table 1 at V_B = -30, 0 and 30V. Mobility T-dependence has been evaluated considering measurements with T ranging from 25°C to 150°C.

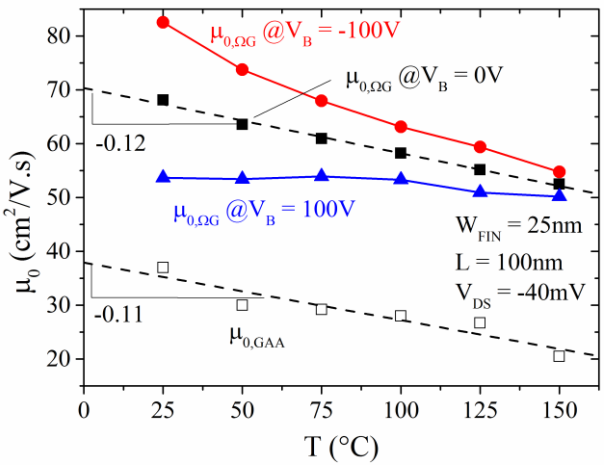


Figure 18. Extracted μ_0 as a function of T for both top GAA- and bottom Ω-NWs of stacked transistors with W_{FIN} = 25nm, L = 100nm and V_{DS} = -40mV. Different V_B values are shown for bottom Ω-NW.

Table 1. $\Delta\mu_0/\Delta T$ for V_B = -30, 0 and 30V for the bottom level of stacked NW and non-stacked Ω-NW with similar dimensions.

	$\Delta\mu_0/\Delta T$ ($cm^2/V.s.°C$)	
	Bottom level Ω-NW W_{FIN} = 25nm, L = 100nm	**Non-stacked Ω-NW W_{FIN} = 20nm, L = 100nm**
V_B = -30V	-0.15	-0.27
V_B = 0V	-0.12	-0.21
V_B = 30V	-0.09	-0.15

IV. CONCLUSIONS

This work detailed the effect of back bias in Ω-gated NWs through experimental measurements and tridimensional numerical simulations. It has been verified the importance of considering V_B dependence on the effective mobility extraction, because μ_0 is significantly affected by the holes concentration reduction and displacement with V_B decrease. A linear behavior between mobility and V_B has been evidenced in non-stacked Ω-NWs and also in the bottom level of stacked NWs. Such dependence must be taken into consideration to correctly describe I_{DS} of narrow NW SOI transistors.

A methodology to separate mobility contributions of each level of stacked NW structure has been proposed by means of V_B variation. The proposed methodology has been validated using experimental and tridimensional simulated data. The method is valuable for technology optimization, once it has shown to be a powerful tool for electrical parameters extraction, allowing μ_0 accurate description in a wide range of V_B. Lower μ_0 extracted for top level GAA-NWs in comparison to bottom Ω-NWs are in agreement with results in literature, due to stronger (100)/[110] surface contribution and surface roughness degradation.

The proposed method has been also applied in stacked NWs up to 150°C to study μ_0 T-dependence with V_B. Results are consistent with physical effects known for mobility scattering mechanisms dependence on temperature, validating the proposed methodology. Mobility dependence on T for Ω-NWs remarkably varies with V_B in the studied range.

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